



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Liu, et al.**

Serial No.: 09/575,055

Filed: May 19, 2000

For: **"Method for Selective Fabrication
of High Capacitance Density Areas
in a Low Dielectric Constant
Material and Related Structure"**

Art Unit: 2825

Examiner: Chuong A. Luu

#5/Election
& Amdt a
9/15/01
V.VarnallAMENDMENT AND RESPONSEHonorable Commissioner of
Patents and Trademarks
Washington, D.C. 20231RECEIVED
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TECHNOLOGY CENTER 2800

Dear Sir/Madam:

This is in response to the Office Action dated August 28, 2001 in the above-referenced patent application. Please enter and consider the following amendments and remarks.

In the Claims:

Please cancel claims 24-27.

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438, 238, 239, 240, 241
(243) 246, 247
386, 389, 390
387